Gas Plasma Reactor

Compact, Barrel Type, Low Temperature Ashing Device

PR200 / PR300-115V PR300-220V / PR301-115V PR301-220V

High-frequency 200W 300W (PR200) (PR300/301)

Reaction chamber | Ø100 x 160mm x 1 | Ø64 x 160mm x 3 | Ø118 x 160mm x 1 | (PR300) | (PR301)

Wide range of application from ashing, etching, dry cleaning, etc.

Features

- Isotropy barrel type
- Compact, space saving design
- Capable of removing coated organic matter
- Adjustable RF suitable for various applications
- Outstanding operability and safety
- Can be set for a wide range of output conditions to handle a variety of testing samples

Applications

 Functionalization of the polymeric material surface improves adhesion

Oxidation reaction generates functional groups -OH, >C=O, -COOH on the surface (very small amount of water and carbon dioxide will impact)

- In nitrogen plasma, a nitrogen atom is incorporated onto the surface, generates a functional group -NH₂
- Resist peeling
- Surface modification of materials (metals, polymers, films, ceramics, etc.)
- Asbestos pre-processing (ashing of membrane filter)
- Low-temperature ashing (polymer material, coal, food, etc.)
- PDMS chips bonding to glass and PDMS substrate
- Production of semiconductors and analysis work



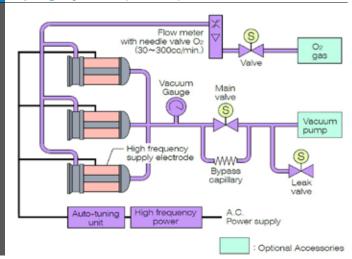


Specifications

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Model	PR200	PR300-115V PR300-220V	PR301-115V PR301-220V
Plasma mode	Direct plasma (DP)		
High frequency output	Max. 200W	Max. 300W (100W x 3 chambers)	Max. 300W
Oscillation frequency	13.56MHz		
Tuning method	Auto matching	Manual biaxial	
Reaction chamber	Pyrex glass, ø100×160mm x 1 chamber	Pyrex glass, ø64×160mm×3 chambers	Pyrex glass, ø118×160mm x 1 chamber
Reaction gas	1 system (oxygen), flow meter control with dry air purge gas		
Control system	Manual leak valve	Auto pressure reduction, auto leak valve	
Piping material	Stainless steel, Teflon	Stainless steel, Teflon, Copper and Brass	Stainless steel, Teflon
External dimensions(W×D×H)	350 x 400 x 500mm	438 × 520 × 556mm	438 × 520 × 660mm
Weight	~25kg	~36kg	~34kg
Power source (50/60Hz)	AC115V 13A	AC115 6.1A with plug AC220V 3.2A no plug	AC115 6.1A with plug AC220V 3.2A no plug
Optional accessories	Sample dish, vacuum pump	Sample dish, stand, shelf, vacuum pump	·

Operation Flowchart Main switch Power switch Pump switch Predecompression Evacuation Reaction Output switch Output switch Output switch ON Gas valve OPEN Purge gas Purge gas Normal Pressure Purge gas Stop Termination

Piping System (PR300)



Example application: asbestos analysis pre-processing



Control Panel



Chamber



PR200 1 chamber (ø100 x 160mm)



PR300 3 chambers (ø64 x 160mm) Contamination free



PR301 1 chamber (ø118 x 160mm)

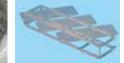
Interior



The gas plasma equipment has a wide range of applications from ashing, etching, dry cleaning, etc.

Accessories







Sample dish Sample shelf for PR3

Sample shelf for PR300 Sample shelf for PR301